

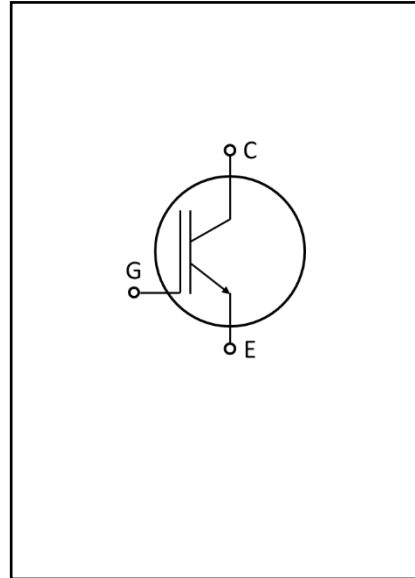
## IGBT Chip

### Features:

- 1200V Trench & Field stop technology
- Low switching losses
- Positive temperature coefficient
- Easy paralleling

### Applications:

- Inverter
- Welding machine
- Induction heating



### Mechanical parameters

Die size	9.876 × 9.880	mm <sup>2</sup>
Emitter pad size	See chip drawing	
Gate pad size	1.0839 × 1.0449	
Area total	97.57	
Thickness	120	μm
Wafer size	200	mm
Max. possible chips per wafer	255	
Passivation front side	Polyimide	
Pad metal	AlCu with Ti/TiN (4μm & 300A/1000A)	
Backside metal	Al/Ti/Ni/Ag	

## Maximum Ratings

Parameter	Symbol	Value	Unit
Collector-Emitter voltage	$V_{CE}$	1200	V
DC collector current	$I_C$	100	A
Operating junction temperature	$T_{vj}$	-40 ... +175	°C
Gate emitter voltage	$V_{GE}$	±20	V
Short circuit data	$t_{SC}$	10	μs

## Static Characteristics (tested on wafer), $T_{vj}=25^{\circ}\text{C}$

Parameter	Symbol	Conditions	Value			Unit
			Min.	Typ.	Max.	
Collector-Emitter breakdown voltage	$V_{(BR)CES}$	$V_{GE}=0\text{V}, I_C=1\text{mA}$	1200			V
Collector-Emitter saturation voltage	$V_{CEsat}$	$V_{GE}=15\text{V}, I_C=100\text{A}$		2.07	2.47	
Gate-Emitter threshold voltage	$V_{GE(th)}$	$I_C=3.8\text{mA}, V_{GE}=V_{CE}$	5.2	5.8	6.4	
Zero gate voltage collector current	$I_{CES}$	$V_{CE}=1200\text{V}, V_{GE}=0\text{V}$			10	uA
Gate-Emitter leakage current	$I_{GES}$	$V_{CE}=0\text{V}, V_{GE}=20\text{V}$			100	nA
Integrated gate resistor	$r_G^{a)}$			8.23		Ω
Input capacitance	$C_{ies}^{a)}$	$V_{CE}=25\text{V}, V_{GE}=0\text{V},$ $f=100\text{kHz}$		5.48		nF
Reverse transfer capacitance	$C_{res}^{a)}$			0.22		

**Chip Drawing**

